

10/734,821  
August 27th, 2004  
Reply to Office Action of 06/29/2004

Via Facsimile

**Amendments to the Claims**

This listing of the claims will replace all prior versions:

**Listing of claims:**

1. (Currently Amended) A condensate polisher system comprising consisting of:

a feed water flow;

at least one deep bed polisher, wherein said deep bed polisher comprises resin beads that are substantially exclusively single ion type, wherein said feed water enters said at least one deep bed polisher to produce a semi-purified water flow;

at least one powdered resin polisher, wherein said powdered resin polisher comprises a mixed ion powdered resin;

wherein said at least one powdered resin polisher accepts said semi-purified water flow from said at least one deep bed polisher to produce a purified water flow;

wherein when said mixed ion powdered resin reaches ion absorption capacity said mixed ion powdered resin is disposed of and replaced.

2. (Previously Presented) The system of claim 1, wherein said resins beads are cation type.

3.(Previously Presented) The system of claim 1, wherein the ratio of cation to anion powder in said mixed ion powdered resin is from 1:1 to 1:10 by weight.

4.(Previously Presented) The system of claim 3, wherein the ratio of cation to anion powder in said mixed ion powdered resin is 1:3.

5.(Previously Presented) The system of claim 1, wherein said feed water flow is adjusted to approximately pH 7.

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- 6.(Previously Presented) The system of claim 1, wherein the number of powdered resin polishers in said condensate polisher system is greater than the number of deep bed polishers.
- 7.(Previously Presented) The system of claim 6, wherein said semi-purified water flow is directed to different powdered resin polishers depending on the nature of the semi-purified water flow.
8. (Previously Presented) The system of claim 1, wherein said resins beads and said powdered resin comprises polystyrene.
9. (Previously Presented) The system of claim 1, wherein said resin powder comprises particulates approximately 25 micrometers in size.
10. (Previously Presented) The system of claim 1, wherein said resin beads are from about 500-1000 micrometers in diameter.
11. (Currently Amended) A condensate polisher system comprising consisting of:
  - a feed water flow;
  - at least one deep bed polisher, wherein said deep bed polisher comprises resin beads that are substantially exclusively single ion type, wherein said feed water enters said at least one deep bed polisher to produce semi-purified water;
  - at least one powdered resin polisher, wherein said powdered resin polisher comprises powdered resin is substantially exclusively single ion type opposite to said resin beads;
  - wherein said at least one powdered resin polisher accepts said semi-purified water flow from said at least one deep bed polisher to produce a purified water flow;
  - wherein when said powdered resin reaches ion absorption capacity  
said powdered resin is disposed of and replaced.
12. (Previously Presented) The system of claim 11, wherein said resins beads are cation type.

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13. (Previously Presented) The system of claim 11, wherein the number of powdered resin polishers in said condensate polisher system is greater than the number of deep bed polishers.

14. (Previously Presented) The system of claim 11, wherein said resins beads and said powdered resin comprises polystyrene.

15. (Currently Amended) A condensate polisher system comprising consisting of:  
a feed water flow;

at least one deep bed polisher, wherein said deep bed polisher comprises charged resin beads that are substantially exclusively cation type, wherein said feed water enters said at least one deep bed polisher to produce a semi-purified water flow;

at least one powdered resin polisher, wherein said powdered resin polisher comprises a mixed ion powdered resin;

wherein said at least one powdered resin polisher accepts said semi-purified water flow from said at least one deep bed polisher to produce a purified water flow;

wherein when said mixed ion powdered resin reaches ion absorption capacity said mixed ion powdered resin is disposed of and replaced.

16. (Previously Presented) The system of claim 15, wherein the ratio of cation to anion powder in said mixed ion powdered resin is from 1:1 to 1:10 by weight.

17. (Previously Presented) The system of claim 16, wherein the ratio of cation to anion powder in said mixed ion powdered resin is 1:3.

18. (Previously Presented) The system of claim 15, wherein the number of powdered resin polishers in said condensate polisher system is greater than the number of deep bed polishers.

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19. (Previously Presented) The system of claim 15, wherein said resins beads and said powdered resin comprises polystyrene.
20. (Previously Presented) The system of claim 19, wherein said polystyrene comprises the cation exchange functional group of sulfonate and the anion exchange functional group of amine.

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**Amendments to the Drawings**

The attached sheets include changes to Figs. 1 & 2, specifically the inclusion of a "Prior Art" subheading as suggested by the examiner.

Attachment:

Replacement Sheet

Annotated Sheet showing changes